

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Joo-Ho KIM et al.

Application No. 10/529,044

Group Art Unit: 1794

Confirmation No. 1715

Filed: January 17, 2006

Examiner: Kevin M. Bernatz

For: HIGH DENSITY RECORDING MEDIUM WITH SUPER-RESOLUTION NEAR-FIELD
STRUCTURE MANUFACTURED USING HIGH-MELTING POINT METAL OXIDE OR
SILICON OXIDE MASK LAYER

AMENDMENT

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Office Action mailed October 2, 2008, and having an original due date of January 2, 2009, and a period for response set to expire on March 2, 2009 with a two month extension of time.

The following amendments and remarks are respectfully submitted. Reconsideration of the claims is respectfully requested.